

EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2	ep-962429-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/22 09:54
S2	2	ep-530676-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/22 09:55
S3	2	ep-546302-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/22 09:56
S4	1	wo-02092527-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/22 09:56
S5	2	De-19541014-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/22 09:57
S6	1	"10589157"	US-PGPUB; USPAT	OR	OFF	2008/12/22 09:59
S7	7	((("5411794") or ("5543229") or ("6627317") or ("6689475") or ("20030180546") or ("20040053068") or ("20070172647"))).PN.	US-PGPUB; USPAT	OR	OFF	2008/12/22 10:02
S8	11	(silicon near nitride\$1 si \$1n\$1) near5 substrate\$1 and dielectric near5 oxide \$1 and crn	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/24 10:36

S9	69	(silicon near nitride\$1 si \$1n\$1) same substrate\$1 and dielectric near5 oxide \$1 and crn	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/24 10:46
S10	59	dielectric near (si\$1nx)	US-PGPUB; USPAT	OR	ON	2008/12/31 09:26
S11	666	\$4stoichiometric near (silicon near nitride\$1 si \$1n\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/31 09:30
S12	99	\$4stoichiometric near (silicon near nitride\$1 si \$1n\$1)and substrate near glass	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/31 09:30
S13	36	\$4stoichiometric near (silicon near nitride\$1 si \$1n\$1)same dielectric\$1 and substrate near glass	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/31 09:31
S14	1	("20020064662").PN.	US-PGPUB; USPAT	OR	OFF	2008/12/31 09:41
S15	8	("2005/0123772").URPN.	USPAT	OR	OFF	2008/12/31 10:02
S16	8	("2005/0123772").URPN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/31 10:03
S23	1	wo-0248065-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/31 10:41
S24	1	2002-480323.NRAN.	DERWENT	OR	OFF	2008/12/31 10:41
S27	2	JP-2000132824-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/28 10:12

S29	6	((("20030044652") or ("20040069616") or ("20030031879") or ("20030180546") or ("6689475") or ("5543229")).PN.	US-PGPUB; USPAT	OR	OFF	2010/01/28 10:23
S31	1	wo-0242234-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/01/28 10:44
S33	27892	(silicon near nitride\$1 si \$1n\$1) same substrate\$1 and dielectric near5 oxide \$1	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/28 10:48
S34	7977	(silicon near nitride\$1 si \$1n\$1) same substrate\$1 and dielectric near5 oxide \$1 and (semi\$1metallic \$1CrN NiCrO\$1 chromium near nitride\$1 Ni Cr nickel chromium NiCr)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/28 10:51
S35	43	(silicon near nitride\$1 si \$1n\$1) same substrate\$1 same dielectric near5 oxide \$1 same(semi\$1metallic \$1CrN NiCrO\$1 chromium near nitride\$1 Ni Cr nickel chromium NiCr)near (layer \$1 coating\$1 film\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/28 10:53
S36	992	(silicon near nitride\$1 si \$1n\$1) same substrate\$1 and dielectric\$1 near5 oxide\$1 near(layer\$1 coating\$1 film\$1)and(semi \$1metallic \$1CrN NiCrO\$1 chromium near nitride\$1 Ni Cr nickel chromium NiCr)near (layer\$1 coating \$1 film\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/28 10:54
S37	634	(silicon near nitride\$1 si \$1n\$1) same oxide\$1 near (layer\$1 coating\$1 film\$1) same(semi\$1metallic \$1CrN NiCrO\$1 chromium near nitride\$1 Ni Cr nickel chromium NiCr)near (layer \$1 coating\$1 film\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/28 10:54

S38	415	(silicon near nitride\$1 si \$1n\$1)near (layer\$1 coating\$1 film\$1) same oxide\$1 near(layer\$1 coating\$1 film\$1)same (semi\$1metallic \$1CrN NiCrO\$1 chromium near nitride\$1 Ni Cr nickel chromium NiCr)near (layer \$1 coating\$1 film\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/28 10:55
S39	994	(silicon near nitride\$1 si \$1n\$1)near (layer\$1 coating\$1 film\$1) same substrate\$1 and oxide\$1 near(layer\$1 coating\$1 film\$1)same(semi \$1metallic \$1CrN NiCrO\$1 chromium near nitride\$1 Ni Cr nickel chromium NiCr)near (layer\$1 coating \$1 film\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/28 10:55
S40	50	(silicon near nitride\$1 si \$1n\$1)near (layer\$1 coating\$1 film\$1) near10 substrate\$1 same oxide\$1 near(layer\$1 coating\$1 film\$1)same(semi \$1metallic \$1CrN NiCrO\$1 chromium near nitride\$1 Ni Cr nickel chromium NiCr)near (layer\$1 coating \$1 film\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/28 10:57
S41	220	(silicon near nitride\$1 si \$1n\$1)near (layer\$1 coating\$1 film\$1) same substrate\$1 same oxide\$1 near(layer\$1 coating\$1 film\$1)same(semi \$1metallic \$1CrN NiCrO\$1 chromium near nitride\$1 Ni Cr nickel chromium NiCr)near (layer\$1 coating \$1 film\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/28 10:58

EAST Search History (I nterference)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp

L1	3	((silicon near nitride \$1 si\$1n\$1)near (layer\$1 coating\$1 film\$1) same substrate\$1 same oxide\$1 near(layer\$1 coating\$1 film\$1) same(semi\$1metallic \$1CrN NiCrO\$1 chromium near nitride \$1 Ni Cr nickel chromium NiCr)near (layer\$1 coating\$1 film\$1)).clm.	US-PGPUB; USPAT; UPAD	OR	ON	2010/01/28 14:20
L2	510	((silicon near nitride \$1 si\$1n\$1)near10 (layer\$1 coating\$1 film\$1) and substrate \$1 same oxide\$1 near10(layer\$1 coating\$1 film\$1)and (semi\$1metallic \$1CrN NiCrO\$1 chromium near nitride \$1 Ni Cr nickel chromium NiCr) near10 (layer\$1 coating\$1 film\$1)).clm.	US-PGPUB; USPAT; UPAD	OR	ON	2010/01/28 14:22
L3	49	((silicon near nitride \$1 si\$1n\$1)near2 (layer\$1 coating\$1 film\$1) same substrate\$1 same oxide\$1 near2(layer \$1 coating\$1 film\$1) and(semi\$1metallic \$1CrN NiCrO\$1 chromium near nitride \$1 Ni Cr nickel chromium NiCr)near2 (layer\$1 coating\$1 film\$1)).clm.	US-PGPUB; USPAT; UPAD	OR	ON	2010/01/28 14:23

1/ 28/ 2010 2:26:45 PM

C:\ Documents and Settings\ Ixu\ My Documents\ EAST\ Workspaces\ 10589157.wsp